

PUBLICATION NUMBER : 04318168  
PUBLICATION DATE : 09-11-92

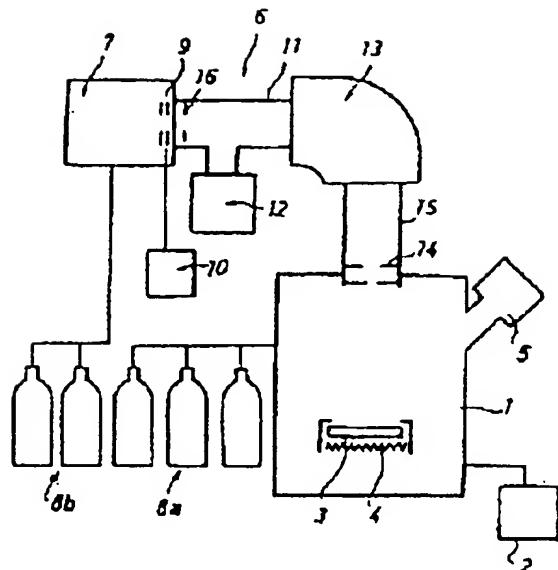
APPLICATION DATE : 17-04-91  
APPLICATION NUMBER : 03085540

APPLICANT : ISHIKAWAJIMA HARIMA HEAVY IND  
CO LTD;

INVENTOR : KUWABARA HAJIME;

INT.CL. : C23C 16/00 C23C 14/48

TITLE : ION COMPOSITE CVD METHOD AND  
DEVICE THEREFOR



ABSTRACT : PURPOSE: To simultaneously use a CVD method and ion implantation.

CONSTITUTION: The thin film is formed on a base plate in a low pressure region by a CVD method and also ions are implanted into this film at high speed through a differential pressure regulating means. Ion mixing or high-speed neutral particles are made incident on the film. Further this device is equipped with both a vacuum vessel 1 for forming the film on the base plate by a CVD method and an ion implantation device 6 described below. This ion implantation device 6 is connected to the vacuum vessel 1 via a differential pressure exhaust part and used for irradiating the film on the base plate 3 during film formation due to the CVD method with high-speed ions and high-speed neutral particles.

COPYRIGHT: (C)1992,JPO&Japio